EXHIBIT F



Case 6:20-cv-00636-ADA Document 145-6 Filed 12/10/21

July 25, 2005

sputtering in transition mode.

Claim 85 (New): A method of depositing a film on a substrate, comprising: providing a process gas between a target and a substrate; providing pulsed DC power to the target; providing a magnetic field to the target; and wherein a material is deposited on the substrate, and an oxide film is formed by reactive

December 21, 2005

Claim 85 (Currently amended): A method of depositing a film on a substrate, comprising:

providing a process gas between a target and a substrate;

providing pulsed DC power to the target;

providing a magnetic field to the target; and

wherein a material is deposited on the substrate, and an oxide film is formed by reactive sputtering in-transition mode a mode between a metallic mode and a poison mode.

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